

Supporting Information for

Internal nanostructure diagnosis with hyperbolic phonon polaritons in hexagonal boron nitride

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1. Simulation of hyperbolic phonon polaritons in hexagonal boron nitride with/without the internal defect

Collective electromagnetic modes can be identified with the maxima of dissipation, that is the imaginary part of the complex reflectivity $r_p(q, \omega)$ ¹. Our system consists five layers: top hBN, air gap, bottom hBN, SiO₂ and Si for the defective hBN part, and three layers: hBN, SiO₂ and Si for the pristine hBN part. The complex r_p can be derived from Fresnel equations for these multilayer system²:

$$r_{p_{air_hBN_interface}} = \frac{\varepsilon_{hBN_z} k_{air}^z - \varepsilon_{air} k_e^z}{\varepsilon_{hBN_z} k_{air}^z + \varepsilon_{air} k_e^z} \quad (S1)$$

$$r_{p_{hBN_SiO2_interface}} = \frac{\varepsilon_{SiO2} q_e^z - \varepsilon_{hBN_z} q_{SiO2}^z}{\varepsilon_{SiO2} q_e^z + \varepsilon_{hBN_z} q_{SiO2}^z} \quad (S2)$$

$$r_{p_{SiO2_Si_interface}} = \frac{\varepsilon_{Si} q_{SiO2}^z - \varepsilon_{SiO2} q_{Si}^z}{\varepsilon_{Si} q_{SiO2}^z + \varepsilon_{SiO2} q_{Si}^z} \quad (S3)$$

$$r_{p_{SiO2}} = \frac{r_{p_{hBN_SiO2_interface}} + r_{p_{SiO2_Si_interface}} e^{i2q_{SiO2}^z d_{SiO2}}}{1 + r_{p_{hBN_SiO2_interface}} r_{p_{SiO2_Si_interface}} e^{i2q_{SiO2}^z d_{SiO2}}} \quad (S4)$$

where ε is the permittivity along the indicated axis in each layer and q represents the directional momentum of the photon in each layer. The subscript “e” stands for “extraordinary ray” of hBN which is optically uniaxial.

By tracking the maxima of complex reflectivity $r_p(q, \omega)$, we can simulate the hyperbolic phonon polaritons in Figures 2 and 3 of the main text.

2. Numerical modeling of polaritons and reflection, transmission and scattering

Numerical modelling of polaritons in hBN was performed using COMSOL Multiphysics. For this purpose, we designed a model of the cross-section of the hBN slab with a defect, as shown in Fig. 4C in the main text. The lowest-order hBN polaritons^{2, 3} were excited from the left-side of hBN Region 1 using a numerical port (Port 1)⁴. Upon reaching the interior defect, the polariton energy get transmitted into hBN Region 2, reflected back to hBN Region 1 and scattered into higher-order polaritons. The output ports (Port 1 and Port 2 at the right-side of hBN Region 2) were configured to receive only the lowest-order mode: we performed the simulation on the hBN slab with a large lateral size such that only the lowest-order hBN polaritons can reach these ports while the higher-order polaritons get damped.

To obtain the Reflection R and Transmission T at the defect, we applied the same procedure as in Ref. ⁴. Briefly, hBN Region 1 and 2 support polaritons with effective indexes $n_i = n_i' - jn_i''$

($n_i', n_i'' > 0$ where $i = 1, 2$ is the region/port number), the scattering parameters at the defect: \tilde{S}_{ij} , can be evaluated from the scattering parameters at the ports, S_{ij} , as⁵:

$$\begin{aligned}\tilde{S}_{ii} &= S_{ii} e^{j2k_0 n_i L_i} \\ \tilde{S}_{ij} &= S_{ij} e^{jk_0(n_i L_i + n_j L_j)},\end{aligned}$$

where $k_0 = \omega / c$ is the free-space photon momentum and L_i is the distance between Port i and the defect. The reflection and transmission coefficients are:

$$\begin{aligned}R &= |S_{11}|^2, \\ T &= |S_{21}|^2.\end{aligned}$$

The energy scattered into higher-order polaritons can be obtained with $S = 1 - R - T$.

References

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